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United States Patent [19]

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Yamamoto et al.

[45] Date of Patent: **** Nov. 29, 1994**

[54] **PROCESSING MACHINE FOR ELECTRON BEAM LITHOGRAPHY SYSTEM**

[56] **References Cited**

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Attorney, Agent, or Firm—Antonelli, Terry, Stout & Kraus

[**] Term: **14 Years**

[57] CLAIM

The ornamental design for a processing machine for electron beam lithography system, as shown.

[21] Appl. No.: **4,586**

DESCRIPTION

[22] Filed: **Feb. 8, 1993**

FIG. 1 is a front, top and right side elevational perspective view of a processing machine for electron beam lithography system showing our new design; FIG. 2 is a front elevational view thereof; FIG. 3 is a left elevational view thereof; FIG. 4 is a right elevational view thereof; FIG. 5 is a top plan elevational view thereof; FIG. 6 is a bottom plan elevational view thereof; FIG. 7 is a rear elevational view thereof; and, FIG. 8 is a rear, top and left side perspective view thereof.

[30] Foreign Application Priority Data

- Nov. 27, 1992 [JP] Japan 34701/1992
- [52] U.S. Cl. **D10/75; D10/46**
- [58] Field of Search 219/121.25, 121.27; 250/492.2, 492.22, 492.23, 492.3, 306, 307, 310, 396 R; D15/199; D10/46, 75; D14/100, 102, 106; D18/50

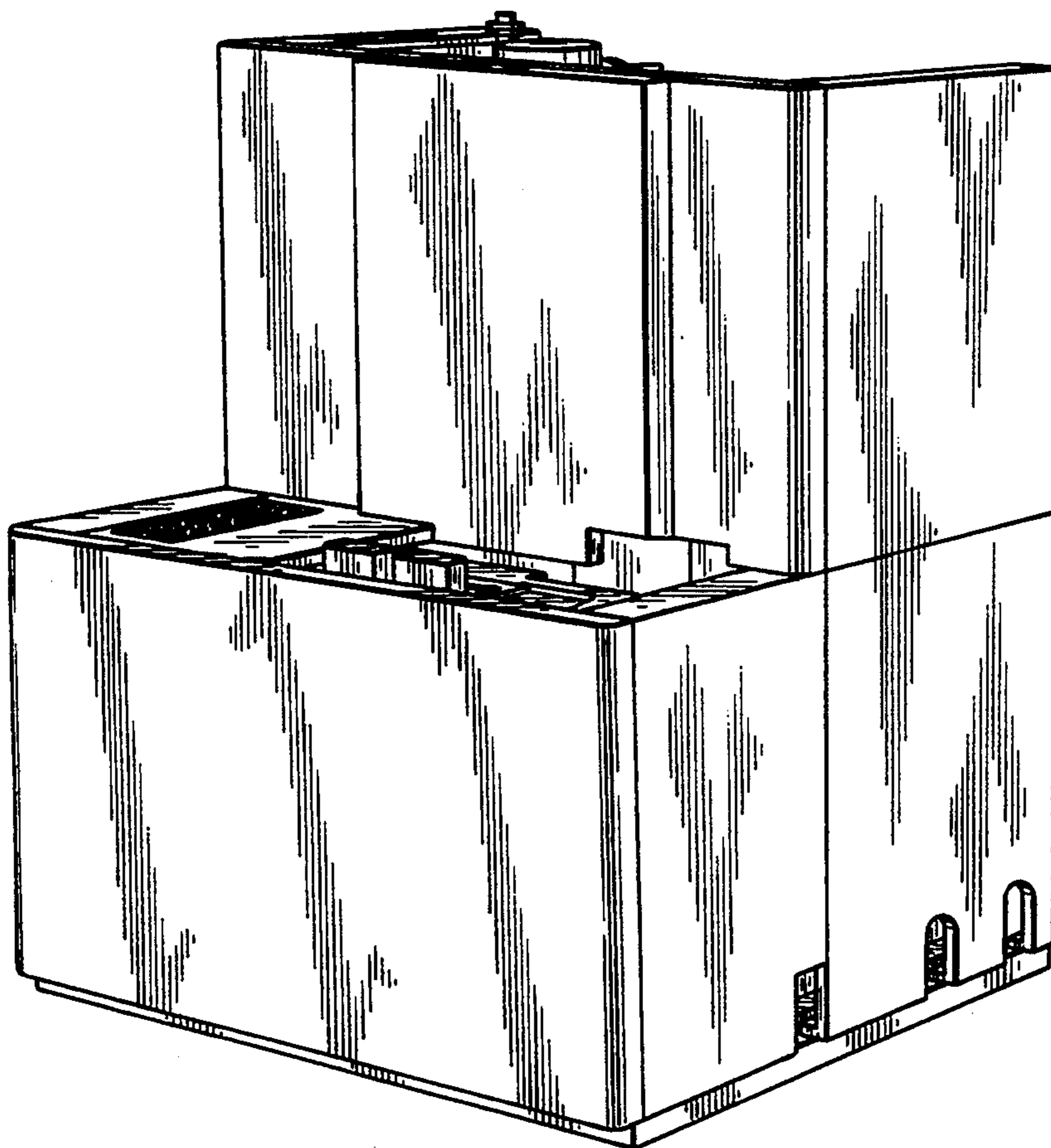


FIG. 2

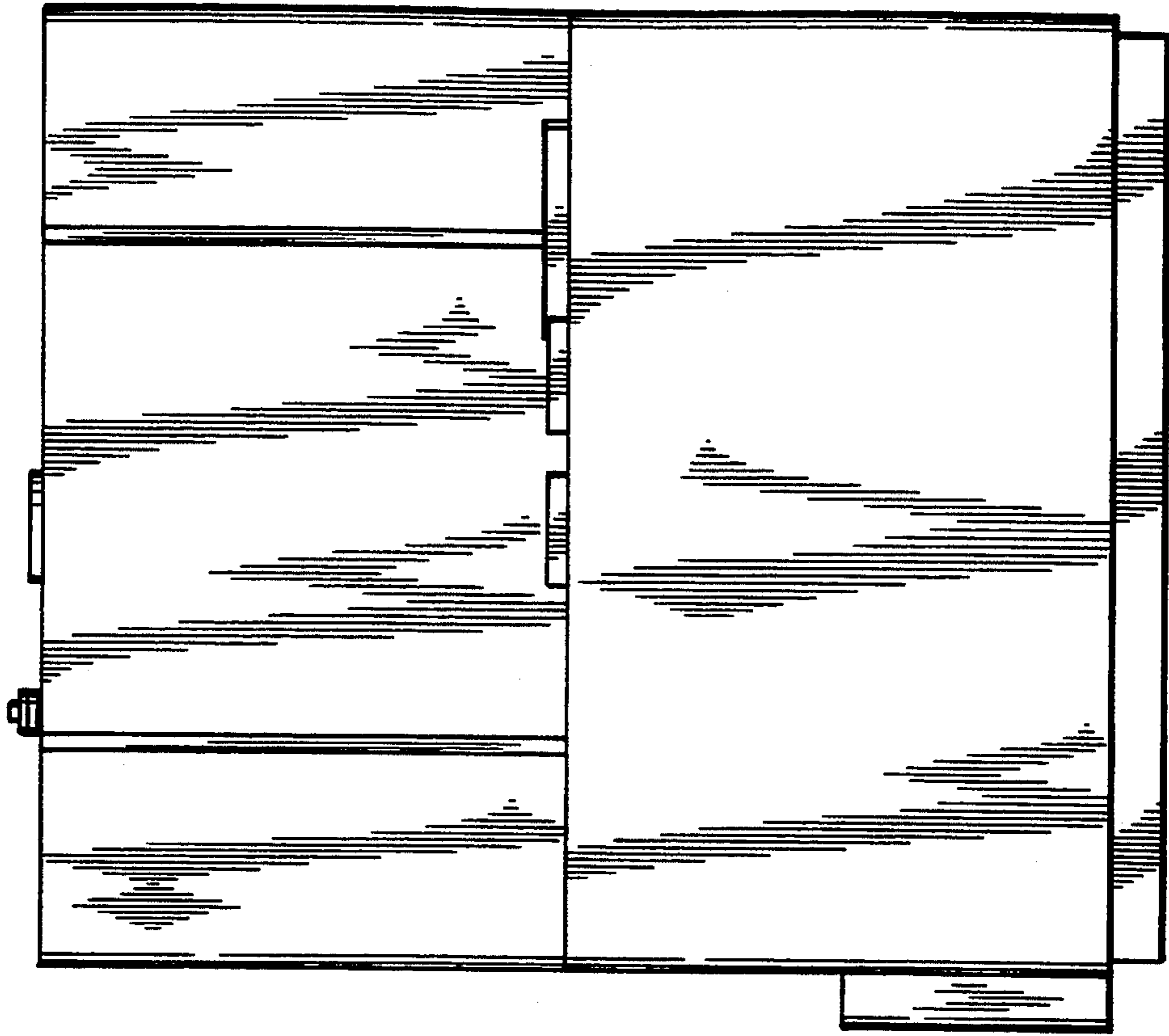


FIG. 1

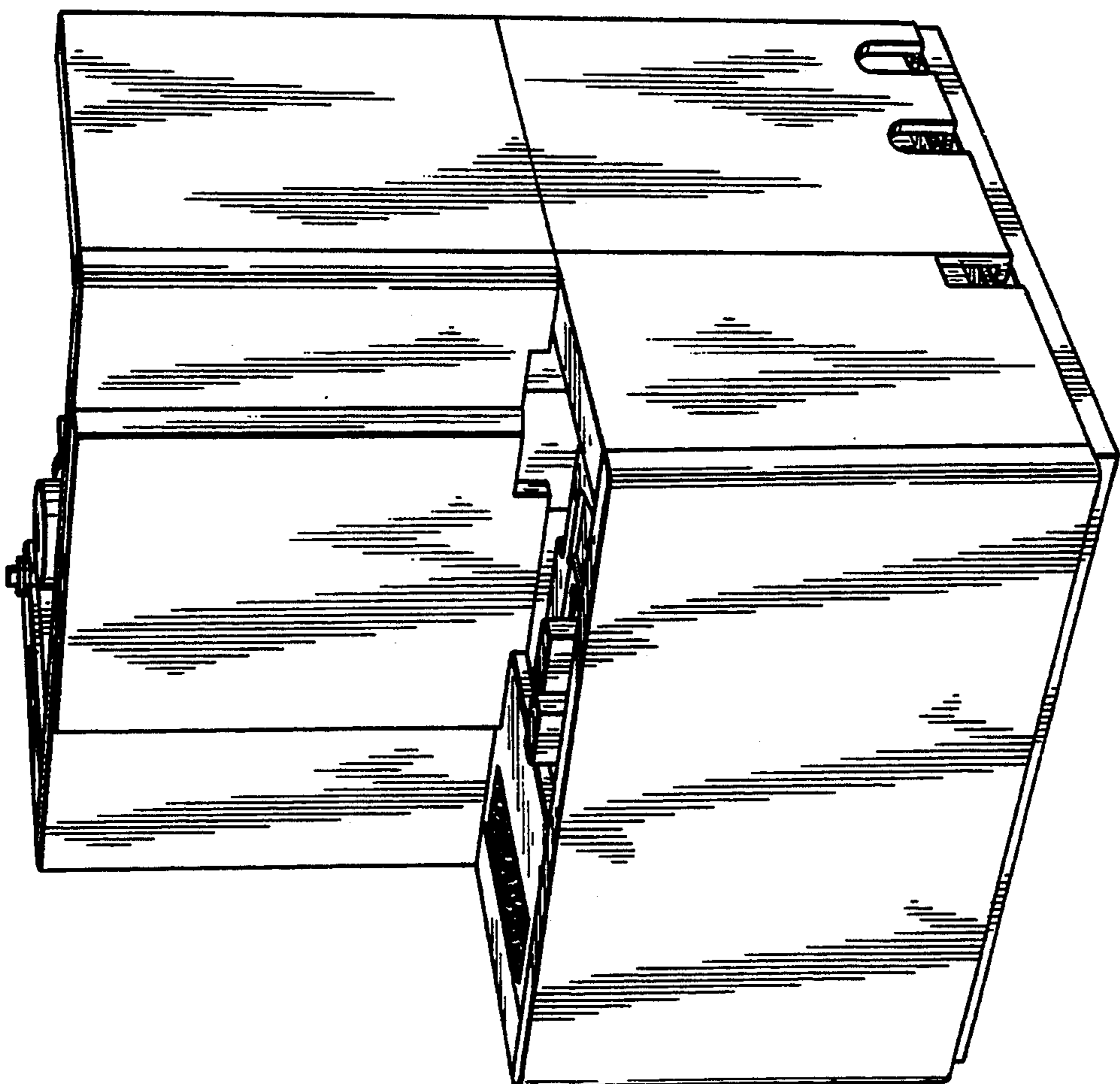


FIG. 4

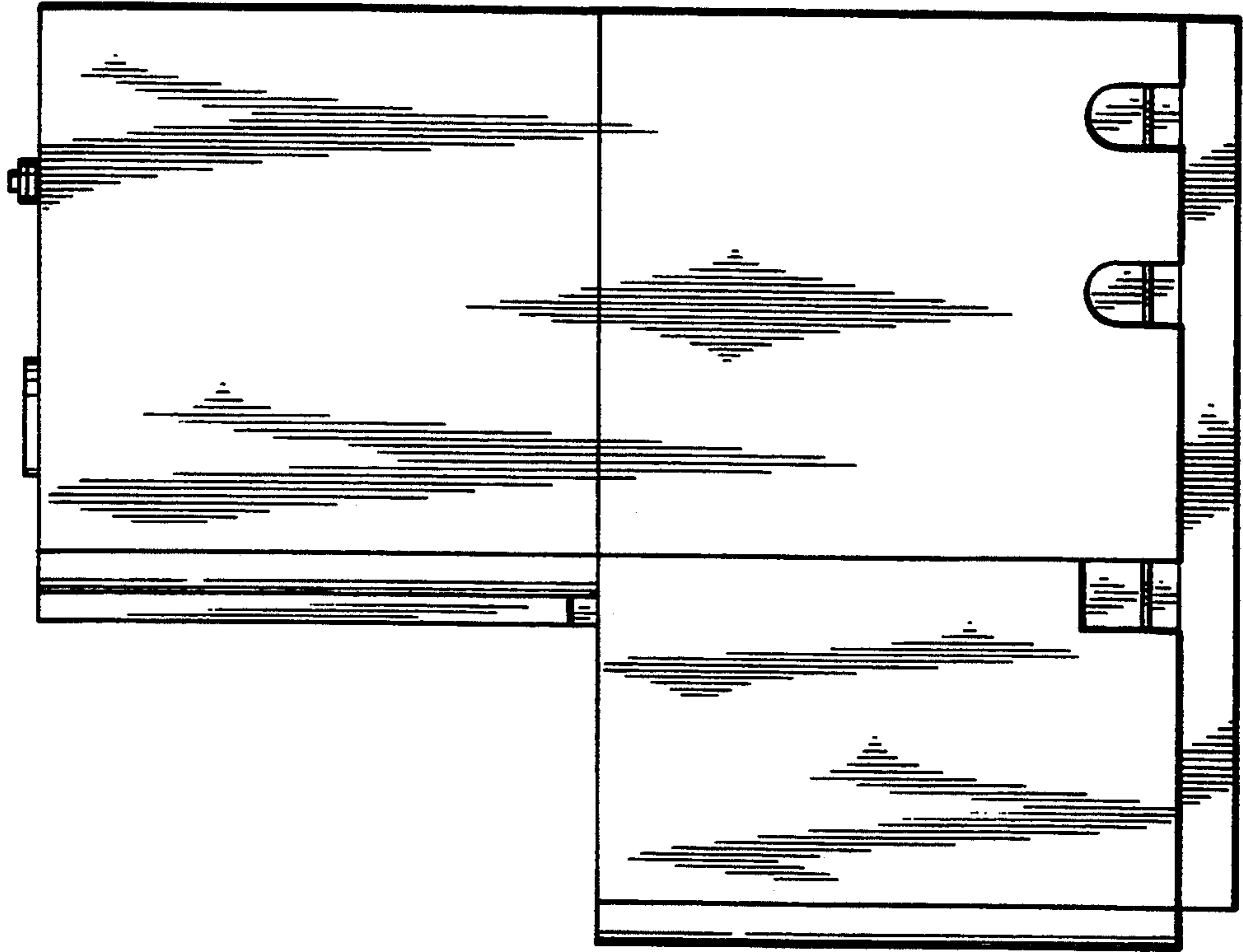


FIG. 3

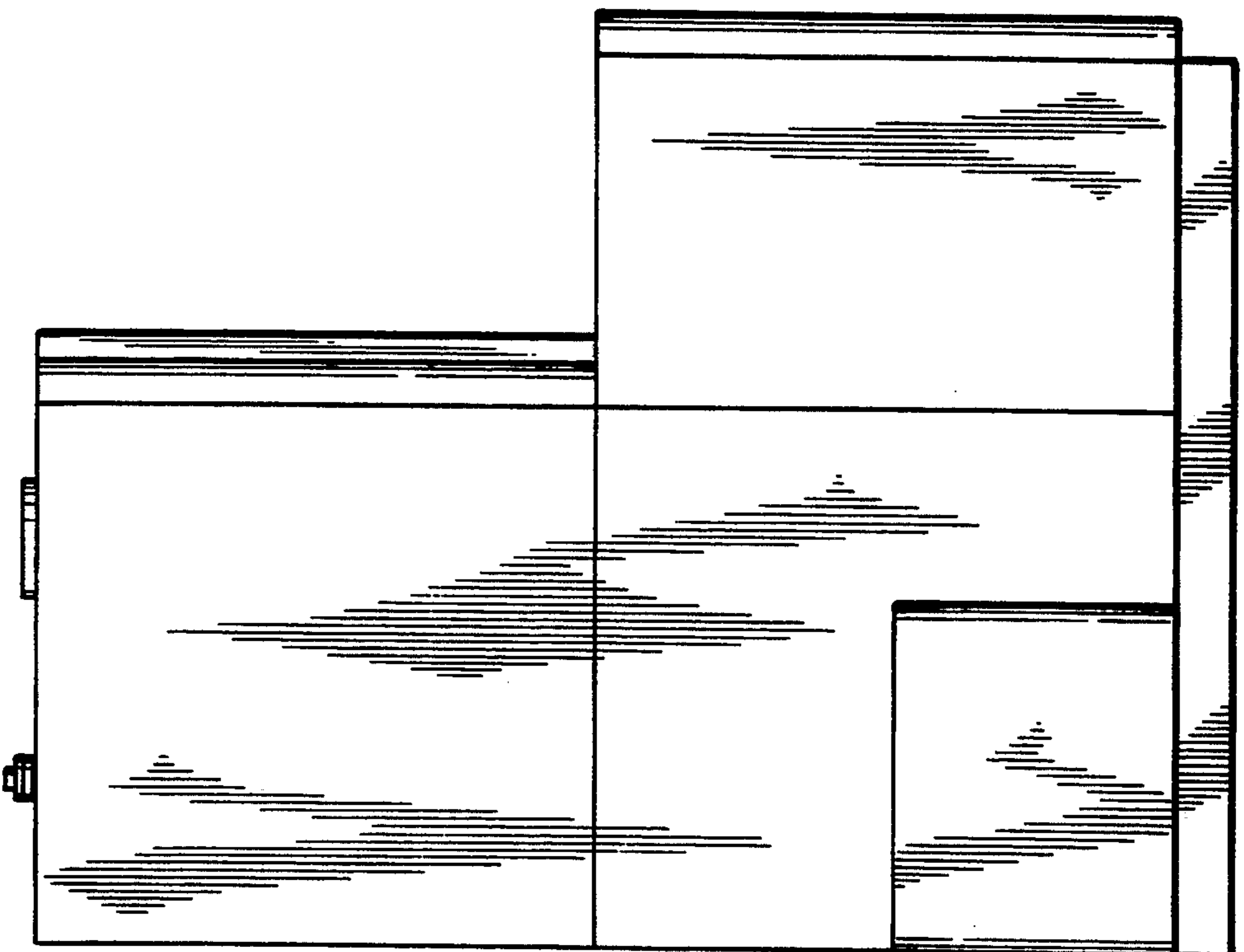


FIG. 5

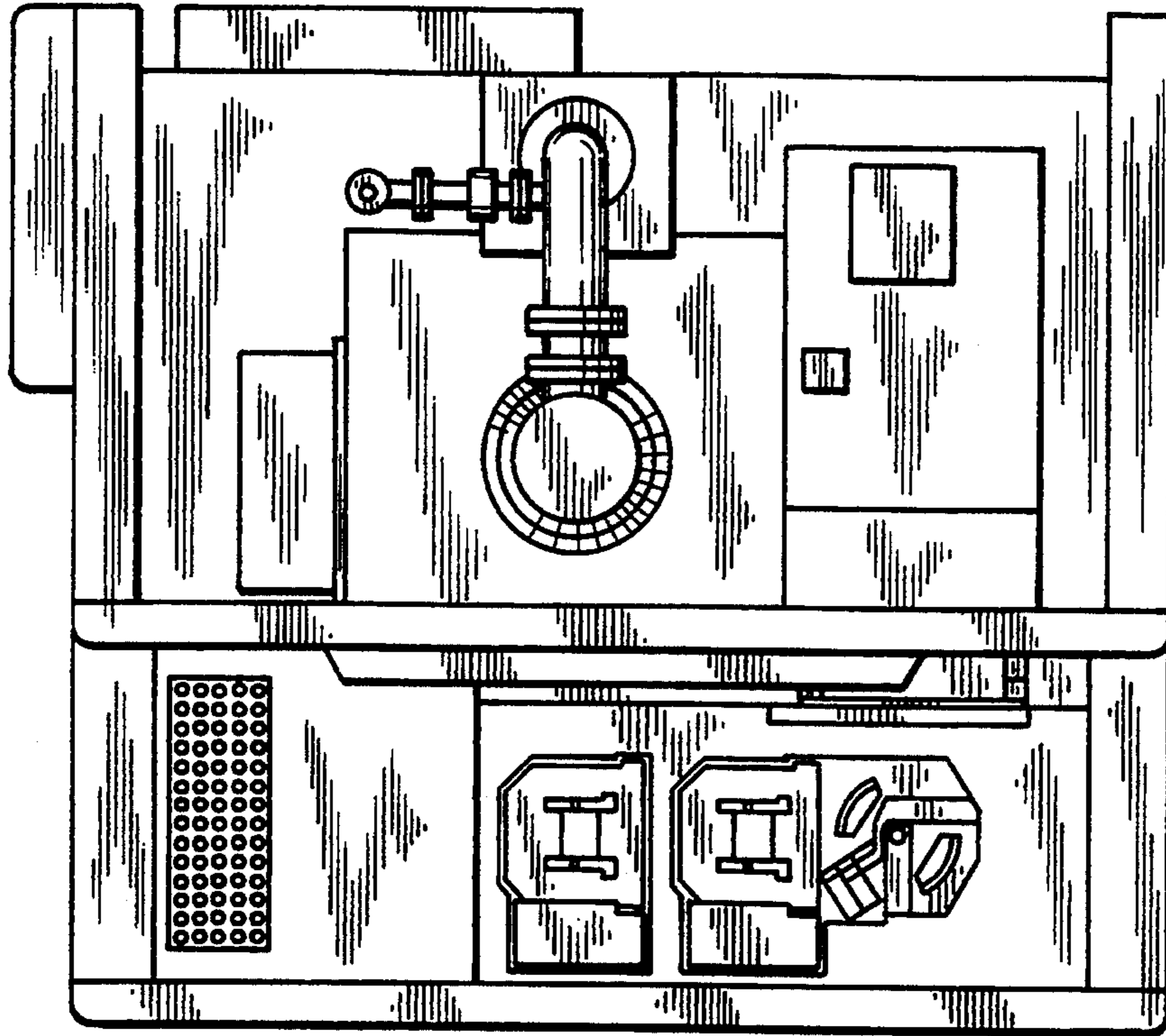


FIG. 6

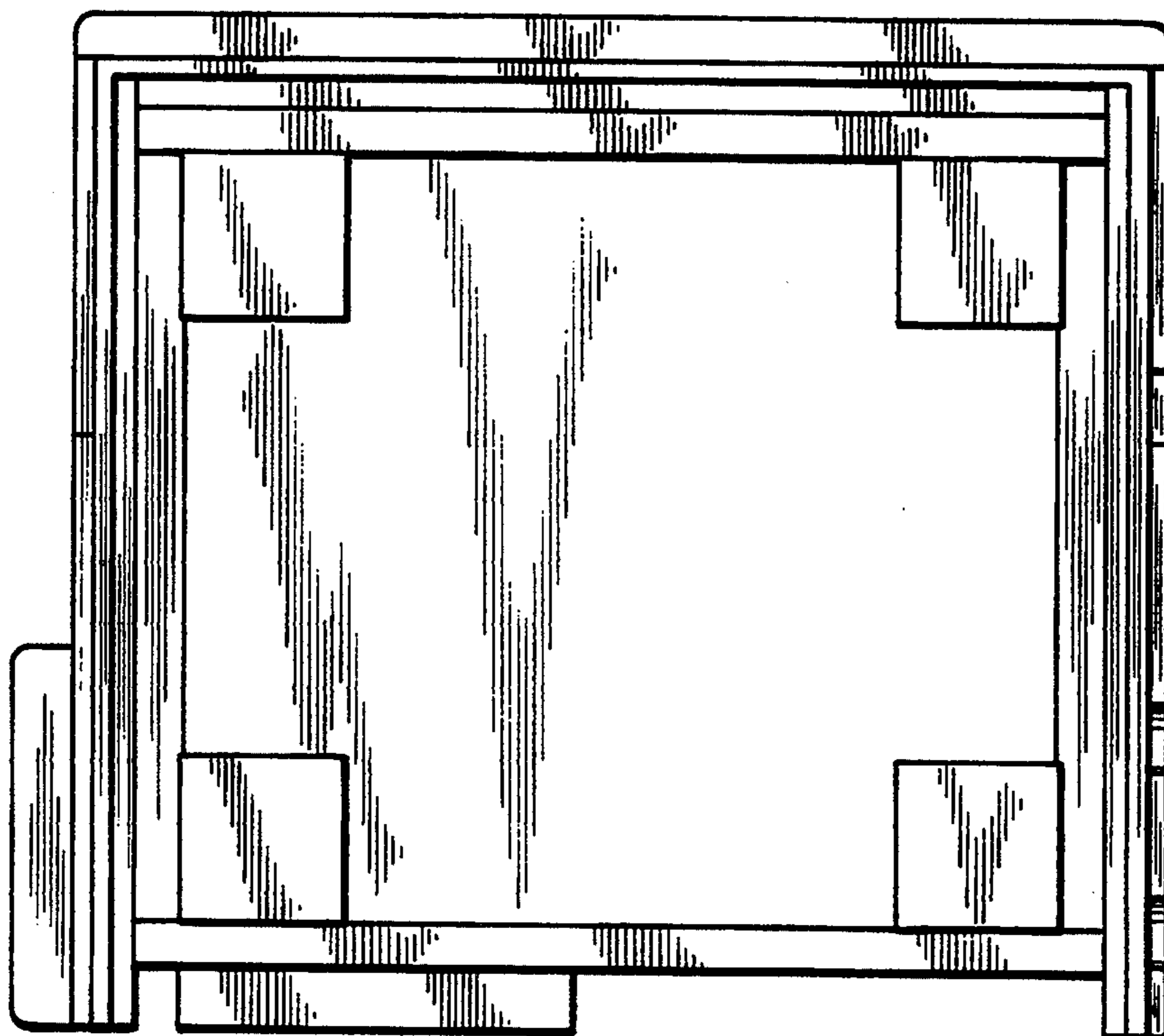


FIG. 7

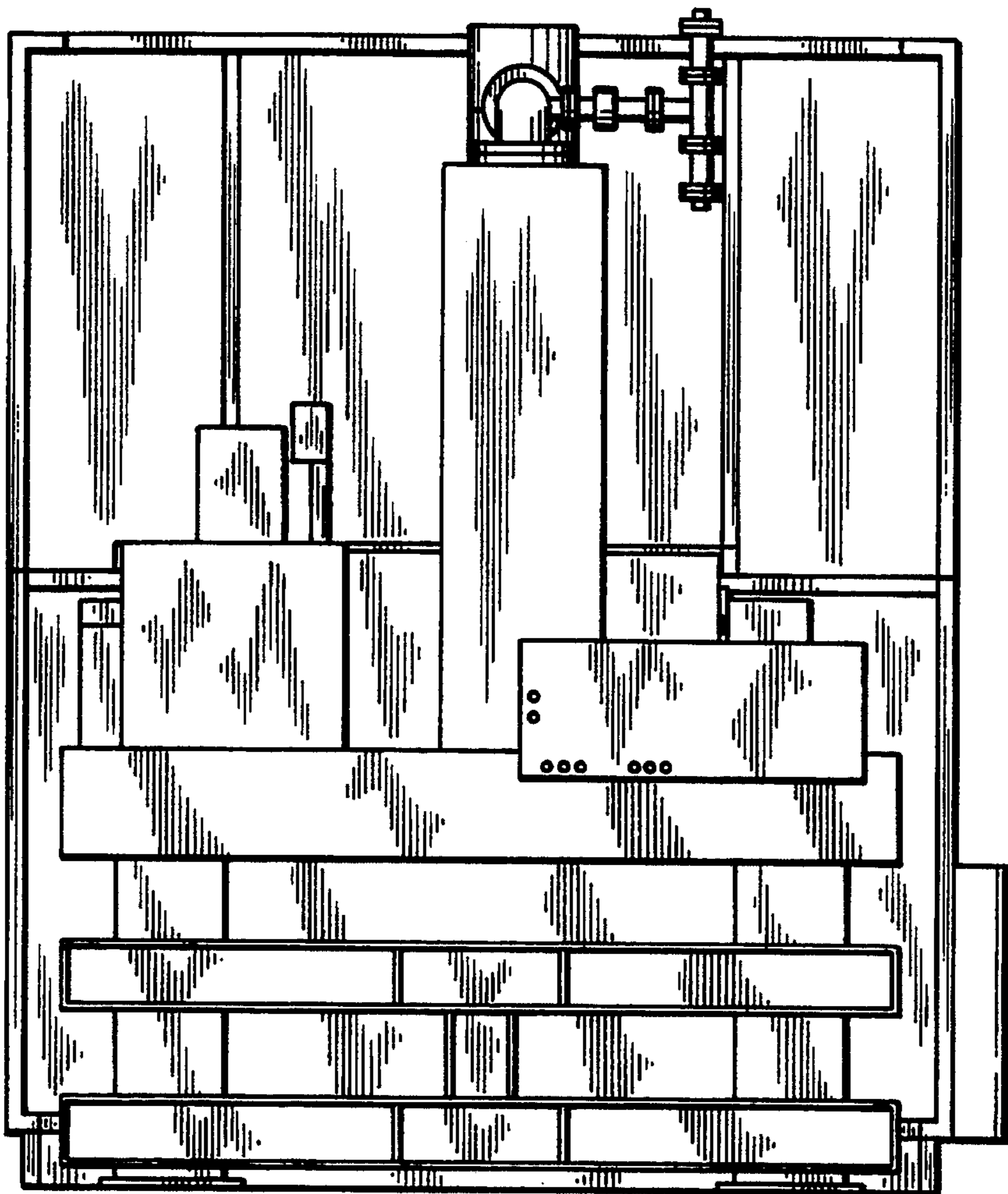


FIG. 8

